



FORM PT-1449 U.S. DEPARTMENT OF COMMERCE										ATTY. DOCKET NO. NAK-127/US		SERIAL NO. 10/607,410		
LIST OF PRIOR ART CITED BY APPLICANT (Use several sheets if necessary)										APPLICANT Li, Gouguang				
										FILING DATE 06/25/2003		GROUP Not yet assigned		
U.S. PATENT DOCUMENTS														
EXAMINER INITIAL		DOCUMENT NUMBER							DATE		NAME		RELEVANT INFORMATION	
	A	4	8	6	6	7	8	2	10/12/1989	Sugie et al				
	B	4	7	5	7	2	0	7	07/12/1988	Chappelow et al				
	C	5	8	6	7	2	7	6	02/02/1999	McNeil et al.				
	D	5	3	6	3	1	7	1	11/08/1994	Mack				
	E	5	1	8	4	0	2	1	02/02/1993	Smith				
	F	5	9	6	3	3	2	9	10/05/1999	Conrad et al.				
	G	5	7	3	9	9	0	9	04/14/1998	Blayo et al.				
	H	5	6	0	7	8	0	0	03/04/1997	Ziger				
	I	6	4	8	3	5	8	0	11/19/2002	Xu et al.				
	J	6	3	4	0	6	0	2	01/22/2002	Johnson et al.				
FOREIGN PATENT DOCUMENTS														
		2- letter code	DOCUMENT NUMBER						DATE		COUNTRY		TRANSLATION	
													YES	NO
	K													
	L													
OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)														
	M		Chopra, K.L., Thin Film Phenomena, p.99 (McGraw Hill)											
			Cynthia B. Brooks, et al., "Process Monitoring of Etched Fused Silica Phase Shift Reticles", Proceedings of the SPIE, 22 nd Annual BACUS Symposium of Technology and Management, September 30-October 4, 2002, Monterey, CA, USA											
	N		Alessandro Callegari and Katerina Babich, "Optical Characterization of Attenuated Phase Shifter", SPIE, Vol. 3050, pp. 504-517											
			Pieter Burggraaf, "Lithography's Leading Edge, Part 1: Phase Shift Technology", February 1992, pp. 43-47											
	O													
	P													
EXAMINER										DATE CONSIDERED <i>22 Sept 2004</i>				
* EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.														